

ACKNOWLEDGEMENT RECEIPT

Electronic Version 1.1

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Title of Invention

HIGH PRESSURE PROCESSING CHAMBER FOR SEMICONDUCTOR SUBSTRATE

Submission Type : Information Disclosure
Statement

Application Number:

09/912844



EFS ID:

76230

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First Named Applicant:

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Attorney Docket Number:

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File Listing:

Doc. Name	File Name	Size (Bytes)	Date Produced (yyyymmdd)
us-ids	SSI00501-usidst.xml	2407	2005-01-18
us-ids	us-ids.dtd	7763	2005-01-18
us-ids	us-ids.xsl	12026	2005-01-18
package-data	SSI00501-pkda.xml	1712	2005-01-18
package-data	package-data.dtd	27025	2005-01-18
package-data	us-package-data.xsl	19263	2005-01-18
Total files size		70196	

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